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(74) Agent: **KOLSTER OY AB**; Iso Roobertinkatu 23, P.O. Box 148, FIN-00121 Helsinki (FI).

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(71) Applicant (for all designated States except US): **ALSTOM (SWITZERLAND) LTD** [CH/CH]; Brown Boveri Strasse 7, CH-5401 Baden (CH).

(72) Inventor; and

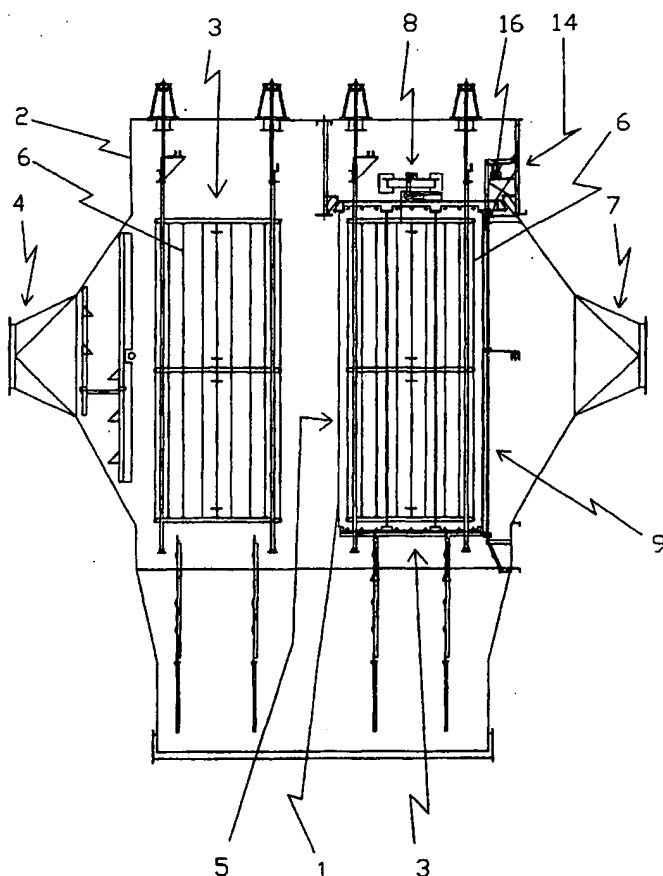
(75) Inventor/Applicant (for US only): **TOLVANEN, Juha** [FI/FI]; Alakiventie 1 d 44, FIN-00920 Helsinki (FI).

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(54) Title: METHOD OF CLEANING ELECTRIC FILTER AND ELECTRIC FILTER



(57) Abstract: The invention relates to a method of cleaning an electric filter and to an electric filter. In the method gas containing particles is fed to a chamber (2) of the electric filter. The gas is further fed to gas channels (5) in an emission system (3) provided in the chamber (2). What is brought about is electric charging of the particles in the gas and attachment to the separation electrode (1). Gas purified of particles is removed from the gas channel (5). The separation electrode (1) is shaken with shaking means (8) to remove the particles attached to the separation electrode (1) therefrom. In this method, the gas flow is limited in such a gas channel (5) which adjoins the separation electrode (1) to be shaken by the shaking means (8) when the separation electrode (1) to be shaken by the shaking means (8) is shaken.

WO 2004/112967 A1



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